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AN 1997:496864 CAPLUS

DN 127:98753

TI Substrates with titanium dioxide films having
photocatalytic activity

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SO Eur. Pat. Appl., 9 pp.

CODEN: EPXXDW

PI EP-784034 A1 970716

DS R: DE, GB

AI 96EP-0114886 960914

PRAI 96JP-0003942 960112

96JP-0101380 960423

96JP-0125167 960521

DT Patent

LA English

IC ICM C03C-017/00

ICS C03C-017/25; C01G-023/053; B01J-037/02

CC 57-1 (Ceramics)

AB The substrates are obtained by: depositing TiO₂ in a film form on a
surface of a substrate (e.g., glass) by contacting the substrate
with a reaction soln. contg. ammonium titanium fluoride, water and
an additive which shifts the following equil. reaction:
(NH₄)₂TiF₆+2H₂O.tautm.TiO₂+4HF+2NH₄F toward a right side, and
calcining the deposited TiO₂ film.

ST substrate titania coating photocatalytic activity

IT Coating process

Coatings

(substrates with titanium dioxide films
having photocatalytic activity)

IT Glass substrates

RL: PRP (Properties); TEM (Technical or engineered material use);

USES (Uses)

(substrates with titanium dioxide films
having photocatalytic activity)

IT 13463-67-7, Titanium oxide (TiO₂), processes

RL: PEP (Physical, engineering or chemical process); PRP

(Properties); TEM (Technical or engineered material use); PROC

(Process); USES (Uses)

(substrates with titanium dioxide films
having photocatalytic activity)